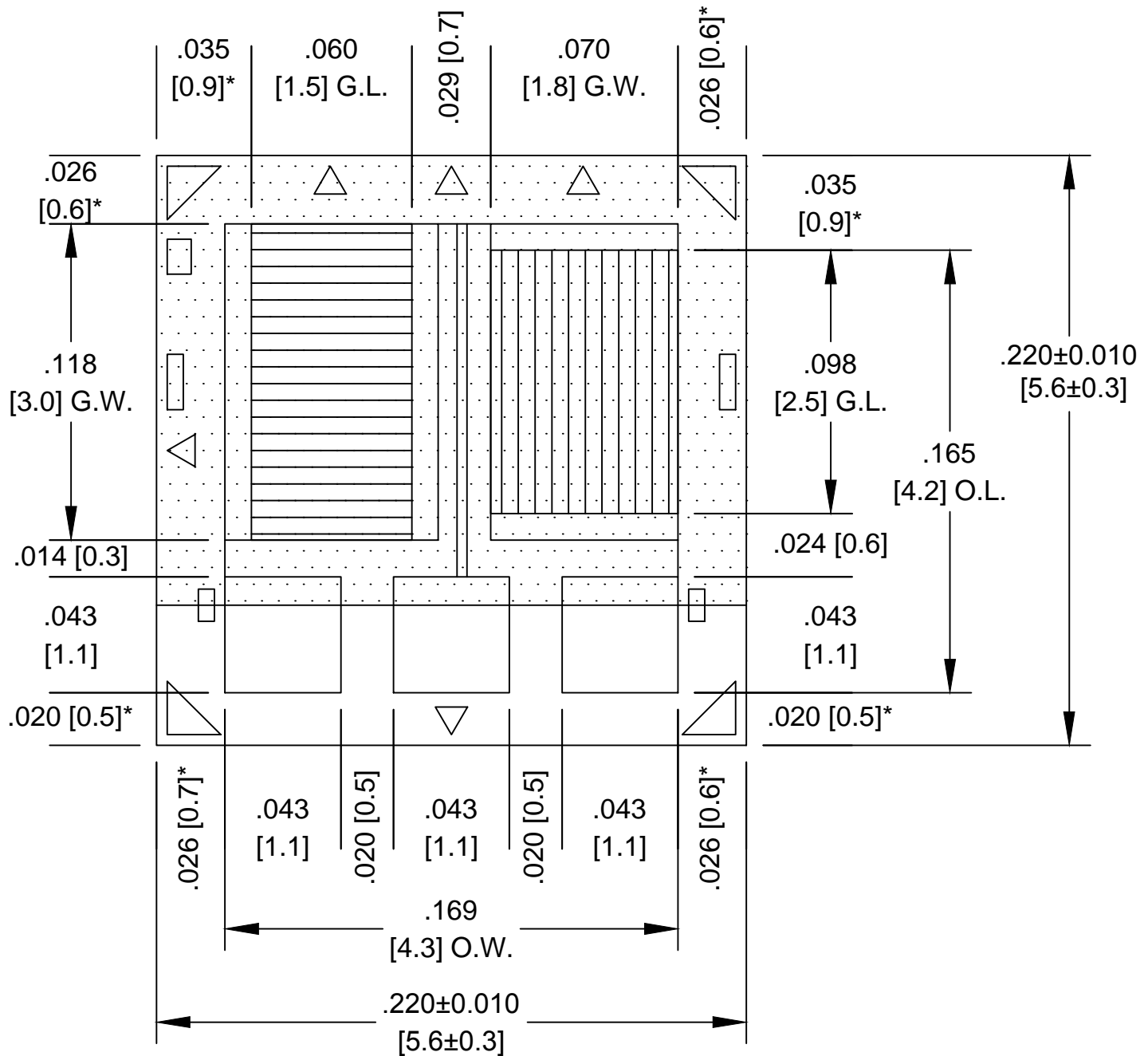


LTR	REVISION	ERN	INITIAL	DATE
B	Add E5 Option		OS	2016-12-13
A	"Balanced to 0.2%" deleted		AR	2015-09-01



* THESE MATRIX RELATED DIMENSIONS ARE ±.0025 [±0.06] REPLACEMENT FOR C-120221-A.

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Micro-Measurements
Raleigh, North Carolina USA



S5189 PATTERN LAYOUT

CONSTRUCTION:

N2A

OPTIONS:

E4, E5

RESISTANCE:

175±0.2%

REFERENCE:

DRAWN BY:

OS

PROJ. ENG.

AH

DATE:

2016-12-13

DATE:

2016-12-13

SCALE:

N.T.S.

DWG. #

MS-S5189-10251

ALL DIMENSIONS ARE IN INCHES [mm].

REVISION:

B